

L Number	Hits	Search Text	DB	Time stamp
-	7	(substrate same (insulating or insulator or dielectric) same lectrode same (black near (matrix r matrices)) same transparent same protrusi n)	USPAT; US-PGPUB; EPO; JP ; DERWENT; IBM_TDB	2003/01/26 12:40
-	8	(substrate same (insulating or insulator or dielectric) same (black near (matrix or matrices)) same transparent same protrusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:41
-	3	(substrate same (insulating or insulator or dielectric) same (black near (matrix or matrices)) same transparent same protrusion) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:42
-	8522	(black near (matrix or matrices))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:42
-	4513	((black near (matrix or matrices))) and transparent	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:42
-	2902	((((black near (matrix or matrices))) and transparent) and pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:42
-	2729	(((((black near (matrix or matrices))) and transparent) and pixel) and substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:43
-	1228	((((((black near (matrix or matrices))) and transparent) and pixel) and substrate) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:43
-	114	((((((((black near (matrix or matrices))) and transparent) and pixel) and substrate) and organic) and protrusion	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:43
-	111	(((((((((black near (matrix or matrices))) and transpar nt) and pix l) and substrate) and rganic) and pr trusi n) and c l r	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:43

-	106	(((((((black n ar (matrix or matrices))) and transparent) and pixel) and substrate) and rganic) and protrusi n) and c l r) and lectr d	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:44
-	28	(((((((black n ar (matrix r matrix s))) and transparent) and pixel) and substrate) and organic) and protrusion) and color) and electrode) and (black near (matrix or matrices)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/26 12:44

L Number	Hits	Search T xt	DB	Tim stamp
-	2731	(transpar nt n ar electro d) n ar10 (insulating r insulat r r dielectric) near10 substrat	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:35
-	2	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) near5 (transparent near electrode) near5 protrusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:37
-	4	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) near10 (transparent near electrode) near10 protrusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:40
-	4	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) near20 (transparent near electrode) near20 protrusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:41
-	3	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) same (transparent near electrode) same protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:42
-	3	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) same (transparent near2 electrode) same protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:42
-	3	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) same (transparent near3 electrode) same protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:43
-	4	((transparent near electrode) near10 (insulating or insulator or dielectric) near10 substrate) and ((black near (matrix or matrices)) same (transparent near3 electrode) same protrusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:43
-	10	((black near (matrix or matrices)) same (transparent near3 electrode) same protrusion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:45
-	1	((black near (matrix r matric s)) sam (transpar nt n ar3 l ctr d) sam pr trusi n)) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:45

-	6	(((black n ar (matrix r matric s)) sam (transpar nt near3 l ctr d) sam protrusion)) and pix l	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:45
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	130	<p>(US-6504592-\$ r US-6476890-\$ r US-6476898-\$ r US-6437847-\$ or US-6441873-\$ r US-6476882-\$ or US-6392728-\$ r US-6323594-\$ r US-6266121-\$ r US-6215243-\$ or US-6239856-\$ or US-6208394-\$ r US-6175395-\$ or US-6163358-\$ or US-6091472-\$ or US-6069674-\$ or US-6008877-\$ or US-5995190-\$ or US-5999236-\$ or US-5946062-\$ or US-5754267-\$ or US-5805249-\$ or US-5815224-\$ or US-5729317-\$ or US-5742371-\$ or US-5640216-\$).did. or (US-5654781-\$ or US-5477351-\$ or US-6433852-\$ or US-6504591-\$ or US-6351078-\$ or US-6498592-\$ or US-6239470-\$ or US-6262784-\$ or US-6243146-\$ or US-6114715-\$ or US-6198520-\$ or US-6162510-\$ or US-6040887-\$ or US-6057896-\$ or US-5870160-\$ or US-5943107-\$ or US-6034747-\$ or US-5478611-\$ or US-5815226-\$ or US-5739880-\$ or US-5721076-\$ or US-6424402-\$ or US-6169293-\$ or US-6275280-\$ or US-5982471-\$ or US-6066448-\$ or US-5952708-\$).did. or (US-5843332-\$ or US-5558927-\$ or US-5619097-\$ or US-6266117-\$ or US-6300152-\$ or US-6509939-\$ or US-6429916-\$ or US-6429917-\$ or US-6476783-\$ or US-6411360-\$ or US-6296750-\$ or US-6373540-\$ or US-6392729-\$ or US-6407782-\$ or US-6356330-\$ or US-6281957-\$ or US-6221543-\$ or US-6224730-\$ or US-6208404-\$ or US-6162654-\$ or US-6157426-\$ or US-6068750-\$ or US-6117294-\$ or US-6118506-\$ or US-6122025-\$ or US-6005651-\$ or US-5956109-\$).did. or (US-5754263-\$ or US-5781254-\$ or US-5689318-\$ or US-5691788-\$ or US-5703668-\$ or US-5633739-\$ or US-5631753-\$ or US-5299041-\$ or US-5495354-\$ or US-5619357-\$ or US-5626796-\$ or US-6388722-\$ or US-6404480-\$ or US-6429059-\$ or US-6433842-\$ r US-6489720-\$ or US-6013930-\$ r US-6121660-\$ r US-6124604-\$ r US-6177974-\$ r US-6204535-\$ or US-6219113-\$ r US-6281952-\$ r US-5529524-\$ or US-5548181-\$ or US-5587623-\$ r US-5847792-\$).did. or (US-6327016-\$).did. or (US-20010049656-\$ or US-20010013913-\$ or US-60020050258-\$).did. r (JP-2001013312-\$ r JP-2001059968-\$ r</p>	<p>USPAT; US-PGPUB; JPO; DERWENT</p>	<p>2003/01/27 09:51</p>
<p>S arch Hist ry 2/9/03 C:\APPS\ ast\workspace</p>	<p>7/13/2004 Page 5 US-60020050258-\$).did. r</p>			

	1	((US-6504592-\$ r US-6476890-\$ r US-6476898-\$ r US-6437847-\$ r US-6441873-\$ or US-6476882-\$ r US-6392728-\$ or US-6323594-\$ or US-6266121-\$ or US-6215243-\$ r US-6239856-\$ or US-6208394-\$ r US-6175395-\$ or US-6163358-\$ or US-6091472-\$ or US-6069674-\$ or US-6008877-\$ or US-5995190-\$ or US-5999236-\$ or US-5946062-\$ or US-5754267-\$ or US-5805249-\$ or US-5815224-\$ or US-5729317-\$ or US-5742371-\$ or US-5640216-\$).did. or (US-5654781-\$ or US-5477351-\$ or US-6433852-\$ or US-6504591-\$ or US-6351078-\$ or US-6498592-\$ or US-6239470-\$ or US-6262784-\$ or US-6243146-\$ or US-6114715-\$ or US-6198520-\$ or US-6162510-\$ or US-6040887-\$ or US-6057896-\$ or US-5870160-\$ or US-5943107-\$ or US-6034747-\$ or US-5478611-\$ or US-5815226-\$ or US-5739880-\$ or US-5721076-\$ or US-6424402-\$ or US-6169293-\$ or US-6275280-\$ or US-5982471-\$ or US-6066448-\$ or US-5952708-\$).did. or (US-5843332-\$ or US-5558927-\$ or US-5619097-\$ or US-6266117-\$ or US-6300152-\$ or US-6509939-\$ or US-6429916-\$ or US-6429917-\$ or US-6476783-\$ or US-6411360-\$ or US-6296750-\$ or US-6373540-\$ or US-6392729-\$ or US-6407782-\$ or US-6356330-\$ or US-6281957-\$ or US-6221543-\$ or US-6224730-\$ or US-6208404-\$ or US-6162654-\$ or US-6157426-\$ or US-6068750-\$ or US-6117294-\$ or US-6118506-\$ or US-6122025-\$ or US-6005651-\$ or US-5956109-\$).did. or (US-5754263-\$ or US-5781254-\$ or US-5689318-\$ or US-5691788-\$ or US-5703668-\$ or US-5633739-\$ or US-5631753-\$ or US-5299041-\$ or US-5495354-\$ or US-5619357-\$ or US-5626796-\$ or US-6388722-\$ or US-6404480-\$ or US-6429059-\$ or US-6433842-\$ or US-6489720-\$ or US-6013930-\$ r US-6121660-\$ r US-6124604-\$ r US-6177974-\$ r US-6204535-\$ r US-6219113-\$ or US-6281952-\$ r US-5529524-\$ or US-5548181-\$ r US-5587623-\$ r US-5847792-\$).did. r (US-6327016-\$).did. r (US-20010049656-\$ r US-20010013913-\$ r US-20010050958-\$).did. r (JP-2001013312-\$ or JP-2001059968-\$ or	USPAT; US-PGPUB; EPO; JP ; DERWENT; IBM_TDB	2003/01/27 09:56
S arch History 2/9/03 C:\APPS\ astlw rkspac	7/13/2004 10:05:58	(US-20010049656-\$ r US-20010013913-\$ r US-20010050958-\$).did. r (JP-2001013312-\$ or JP-2001059968-\$ or		

-	1	(((insulating r insulator or diel ctric) sam substrat) and (transparent n ar electr d) and (bla k near (matrix or matrices)) and pr trusion and (col r near filter) and rganic and (photosensitive) and (lith grahpy r ph toolith graphy) and pix l).ti,ab,clm.	USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:56
-	1	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and (photosensitive) and pixel).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:57
-	1	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:57
-	36	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 09:58
-	28096	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel)) amd (black near (matrix or matrices)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 10:00
-	10	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel)) and (black near (matrix or matrices)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 10:00
-	9	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel)) and (black near (matrix or matrices)).ti,ab,clm.) and substrate.ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 10:01
-	8	(((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel)) and (black near (matrix or matrices)).ti,ab,clm.) and substrate.ti,ab,clm.) and transpar nt.ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 10:01

-	5	(((((((insulating r insulator r diel ctri) sam substrat) and (transparent near lectrod) and (black near (matrix r matrices)) and protrusion and (col r n ar filter) and rganic and pixel)) and (black near (matrix or matric s)).ti,ab,clm.) and substrate.ti,ab,clm.) and transparent.ti,ab,clm.) and data	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 10:02
-	4	(((((((insulating or insulator or dielectric) same substrate) and (transparent near electrode) and (black near (matrix or matrices)) and protrusion and (color near filter) and organic and pixel)) and (black near (matrix or matrices)).ti,ab,clm.) and substrate.ti,ab,clm.) and transparent.ti,ab,clm.) and data) and gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:12
-	1	(black near matrix) and chrome and (color near filter) and (gate near line) and (data near line) and (pixel near electrode) and (redundant near data)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:14
-	3	(black near matrix) and (color near filter) and (gate near line) and (data near line) and (pixel near electrode) and (redundant near data)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:18
-	3559	(transparent near2 electrode near3 (insulating or insulator or dielectric))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:20
-	17	((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:23
-	7	((((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:24
-	1	(((((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transpar nt)) and (protrusi n\$10 near5 organic)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:24

-	1	(((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)	USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:25
-	2	(((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:25
-	2	(((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:26
-	2	(((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive) and pixel	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:26
-	2	(((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive) and pixel) and (black near (matrix or matrices))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:26
-	2	(((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive) and pixel) and (black near (matrix or matrices))) and (transparent near electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:28

-	2	((((((((transparent near2 electr d n ar3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) n ar5 metal)) and ((light n ar (block or blocking or blocked)) n ar5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive) and pixel) and (black near (matrix or matrices))) and (transparent near electrode)) and (black near (matrix or matrices)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 11:28
-	2	((((((((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive) and pixel) and (black near (matrix or matrices))) and (transparent near electrode)) and (black near (matrix or matrices))) and (mask or lithograp\$7 or photolithograp\$7 or photo-litho\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:15
-	0	((((((((transparent near2 electrode near3 (insulating or insulator or dielectric))) and ((light near (block or blocking or blocked)) near5 metal)) and ((light near (block or blocking or blocked)) near5 metal near10 transparent)) and (protrusion\$10 and organic)) and photosensitive) and pixel) and (black near (matrix or matrices))) and (transparent near electrode)) and (black near (matrix or matrices))) and (mask or lithograp\$7 or photolithograp\$7 or photo-litho\$7)) and (qbetech or "qbe tech" or "qbe technologies" or "aqcess technologies")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:16
-	2	qbetech or "qbe tech" or "qbe technologies" or "aqcess technologies"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:44
-	449	((transparent near electrode) near10 (insulating or insulator)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:44
-	648	((transparent near electrode) near10 (insulating or insulator or di I ctric)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:45

-	2	(((transparent near electrode) near10 (insulating or insulator or dielectric)) same (black near (matrix or matrices)) same protrusion).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:46
-	2	(((transparent near electrode) near10 (insulating or insulator or dielectric)) same (black near (matrix or matrices)) same protrusion).clm.) and photosensitive	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:47
-	2	((((transparent near electrode) near10 (insulating or insulator or dielectric)) same (black near (matrix or matrices)) same protrusion).clm.) and photosensitive) and (color near filter)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:48
-	1	((((transparent near electrode) near10 (insulating or insulator or dielectric)) same (black near (matrix or matrices)) same protrusion).clm.) and photosensitive) and (color near filter)) and (method or process).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:48
-	2	((transparent near electrode) and (black near (matrix or matrices)) and (photosensitive) and (etch or etching or etched) and mask and (method or process)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:58
-	6	((transparent near electrode) and (black near (matrix or matrices)) and (etch or etching or etched) and mask and (method or process)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:52
-	3	(((transparent near electrode) and (black near (matrix or matrices)) and (etch or etching or etched) and mask and (method or process)).clm.) and photosensitive	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:51
-	17	((transparent) and (black near (matrix or matrices)) and (etch or etching or etched) and mask and (method or process)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:52
-	4	(((transparent) and (black near (matrix or matrices)) and (etch or etching or etched) and mask and (method or process)).clm.) and photosensitive.clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:52
-	5	(((transparent) and (black near (matrix or matrices)) and (etch or etching or etched) and mask and (method or process)).clm.) and photosensitive	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:53

-	23486	ph t sensitiv .clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:54
-	104	ph tos nsitiv .clm. and (black near (matrix or matrices)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:55
-	87	(photosensitive.clm. and (black near (matrix or matrices)).clm.) and (method or process).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:55
-	12	((photosensitive.clm. and (black near (matrix or matrices)).clm.) and (method or process).clm.) and (etch or etching or etched).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:56
-	11	((((photosensitive.clm. and (black near (matrix or matrices)).clm.) and (method or process).clm.) and (etch or etching or etched).clm.) and transparent	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 12:57
-	4	((transparent near electrode) and (black near (matrix or matrices)) and (photosensitive or resin or epoxy) and (etch or etching or etched) and mask and (method or process)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:00
-	10	((transparent) and (black near (matrix or matrices)) and (photosensitive or resin or epoxy) and (etch or etching or etched) and mask and (method or process)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:01
-	10	((((transparent) and (black near (matrix or matrices)) and (photosensitive or resin or epoxy) and (etch or etching or etched) and mask and (method or process)).clm.) and (mask or masking or masked)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:02
-	10	((((transparent) and (black near (matrix or matrices)) and (photosensitive or resin or epoxy) and (etch or etching or etched) and mask and (method or process)).clm.) and (mask or masking or masked).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:03
-	24	((black near (matrix or matrices)) and (transparent same electrode same substrat) and (mask or masking r masked) and (m th d or proc ss)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:06

-	4	(((black near (matrix or matrices)) and (transparent same electrode same substrate) and (mask or masking or masked) and (method or process)).clm.) and (photo\$15).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:07
-	18	(((black near (matrix or matrices)) and (transparent same electrode same substrate) and (mask or masking or masked) and (method or process)).clm.) and (photosensitive or photoresist or photo-sensitive or photo-resist or resin or epoxy or resist).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:11
-	13	(((black near (matrix or matrices)) and (transparent same electrode same substrate) and (mask or masking or masked) and (method or process)).clm.) and (photosensitive or photoresist or photo-sensitive or photo-resist or resin or epoxy or resist).clm.) and (color near filter)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:13
-	2	(((black near (matrix or matrices)) and (transparent same electrode same substrate) and (mask or masking or masked) and (method or process)).clm.) and (photosensitive or photoresist or photo-sensitive or photo-resist or resin or epoxy or resist).clm.) and (color near filter)) and chrome	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:13
-	8	(((black near (matrix or matrices)) and (transparent same electrode same substrate) and (mask or masking or masked) and (method or process)).clm.) and (photosensitive or photoresist or photo-sensitive or photo-resist or resin or epoxy or resist).clm.) and (color near filter)) and ((black near (matrix or matrices)) near10 (resin or epoxy or photosensitive or photo-sensitive or photoresist or resist or photo-resist)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:20
-	2	(substrate and (insulating or insulator or dielectric) and (gate near line) and (data near line) and (pixel same electrode) and redundant and (switch or switching or switched) and protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:24
-	2	(substrate and (insulating or insulator or dielectric) and (gate near line) and (data near line) and (pixel same electrode) and (redundant near data) and protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:26
-	2	(substrate and (insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel and (redundant near data) and protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:28

-	2	(substrat and (insulating r insulat r or diel ctric) and (gat) and (data) and pix l and (r dundant near data) and pr trusi n).ti,ab,clm.	USPAT; US-P PUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:30
-	2	(substrate and (insulating r insulat r r dielectric) and (gate) and (data) and pixel and (redundant) and protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:30
-	27	(substrate and (insulating or insulator or dielectric) and (gate) and (data) and pixel and protrusion).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:32
-	3	((substrate and (insulating or insulator or dielectric) and (gate) and (data) and pixel and protrusion).ti,ab,clm.) and redundant	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:31
-	4	(substrate and (insulating or insulator or dielectric) and (gate) and (data) and pixel and protrusion and (redundant or repair)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:33
-	3	((substrate and (insulating or insulator or dielectric) and (gate) and (data) and pixel and protrusion and (redundant or repair)).ti,ab,clm.) and (matrix or matrices)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:34
-	2	((substrate and (insulating or insulator or dielectric) and (gate) and (data) and pixel and protrusion and (redundant or repair)).ti,ab,clm.) and (matrix or matrices)) and transparent	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:33
-	1797	((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:37
-	54	((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color ner filter) and transparent and protrusion	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:41

-	28	(((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color near filter) and transparent and protrusion) and (organic) and (photoresist or photo-resist or photolithography or photo-lithography or photosensitive or photo-sensitive or resin or epoxy or mask or masking or masked) and (etch or etching or etched or etchant)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:48
-	25	(((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color near filter) and transparent and protrusion) and (organic) and (photoresist or photo-resist or photolithography or photo-lithography or photosensitive or photo-sensitive or resin or epoxy or mask or masking or masked) and (etch or etching or etched or etchant)) and (color near filter)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:52
-	3	(((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color near filter) and transparent and protrusion) and (organic) and (photoresist or photo-resist or photolithography or photo-lithography or photosensitive or photo-sensitive or resin or epoxy or mask or masking or masked) and (etch or etching or etched or etchant)) and (color near filter)) and image and (scan or scanning) and (transmit or transmitting or transmitted or transmission) and (switch or switching or switched)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:56
-	16	(((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color near filter) and transparent and protrusion) and (organic) and (photoresist or photo-resist or photolithography or photo-lithography or photosensitive or photo-sensitive or resin or epoxy or mask or masking or masked) and (etch or etching or etched or etchant)) and (color near filter)) and (black near (matrix or matrices))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:57

-	12	(((((((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color near filter) and transparent and protrusion) and (organic) and (photoresist or photo-resist or photolithography or photo-lithography or photosensitive or photo-sensitive or resin or epoxy or mask or masking or masked) and (etch or etching or etched or etchant)) and (color near filter)) and (black near (matrix or matrices))) and image	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:59
-	1	(((((((insulating or insulator or dielectric) and (gate near line) and (data near line) and pixel)) and (matrix or matrices) and (color near filter) and transparent and protrusion) and (organic) and (photoresist or photo-resist or photolithography or photo-lithography or photosensitive or photo-sensitive or resin or epoxy or mask or masking or masked) and (etch or etching or etched or etchant)) and (color near filter)) and (black near (matrix or matrices))) and image) and (redundant or repair)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 13:59
-	72	((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:03
-	33	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:04
-	1	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and (organic near black near (matrix or matrices))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:05
-	1	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and (organic same (black near (matrix or matrices)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:10

-	5	(((r dundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal r (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data n ar lin) and (gate near line)) and ((black near (matrix or matrices)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:14
-	2	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and ((black near (matrix or matrices)))) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:20
-	20	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:28
-	18	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and organic) and (pixel same electrode) and (aperture or whole or opening or gap or window)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:29
-	18	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and organic) and (pixel near5 electrode) and (aperture or whole or opening or gap or window)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:30
-	8	(((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and organic) and (pixel near5 electrode) and (aperture or whole or opening or gap or window)) and molecule	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:31
-	5	((((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid n ar crystal) r display)).ti,ab,clm.) and (pix l and image) and (data n ar lin) and (gat n ar lin)) and rganic) and (pix l near5 l ctr de) and (aperture r wh l r p ning r gap r window)) and m l cul) and angle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:31

-	5	(((((((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and organic) and (pixel near5 electrode) and (aperture or whole or opening or gap or window)) and molecule) and angle) and (scan or scanning or scanned)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:32
-	5	(((((((redundant or repair) and gate and data and pixel and (insulating or insulator or dielectric) and (lcd or liquid-crystal or (liquid near crystal) or display)).ti,ab,clm.) and (pixel and image) and (data near line) and (gate near line)) and organic) and (pixel near5 electrode) and (aperture or whole or opening or gap or window)) and molecule) and angle) and (scan or scanning or scanned)) and (transmission or transmit or transmitting or transmitted)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:41
-	36	((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:45
-	1	(((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)).ti,ab,clm.) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:46
-	5	((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:46
-	6	((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)) and organic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:48
-	3	(((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)) and organic) and (pixel near electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:49
-	4	(((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)) and organic) and (pixel)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 15:05

-	3	(((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)) and organic) and (pixel).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:50
-	3	(((insulating or insulator or dielectric) same substrate same transparent same electrode same (light-blocking or (light near (block or blocking or blocked)) same metal same protrusion)) and organic) and (pixel)) and (thin near5 transistor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/27 14:53